

11

32. The system of claim 27, wherein the collected characteristics further comprise process characteristics associated with the first fabrication process.

33. The system of claim 27, wherein collected characteristics further comprise metrology characteristics of the semiconductor device.

34. The system of claim 27, wherein collected characteristics further comprise control characteristics.

35. A system, comprising:

means for providing a set of initial characteristic values associated with the semiconductor device;

means for performing a first fabrication process on the semiconductor device;

means for collecting fabrication data associated with the first fabrication process;

means for replacing at least one of the initial characteristic values with the fabrication data collected for the first fabrication process to generate a first modified set of characteristic values; and

12

means for predicting a first value for at least one electrical characteristic of the semiconductor device based on the first modified set of characteristic values.

36. A system, comprising:

means for storing characteristics associated with the processing of a semiconductor device collected during its fabrication;

means for providing a vector of initial characteristic values associated with the semiconductor device;

means for updating the vector with the collected characteristics; and

means for modeling at least one electrical characteristic of the semiconductor device based on the updated vector.

* * * * *